

REMARKS

Claims 1-32 and 34-40 were presented for examination in the present application and remain pending for consideration upon entry of the instant amendment. Claims 1, 23, and 25 are independent.

Independent claim 1, as well as dependent claims 2-7, 9-14, 16-21, and 36-40, were rejected under 35 U.S.C. §103 over U.S. Publication No. 2002/0019069 to Wada et al. (Wada) in view of U.S. Patent No. 4,374,391 to Camlibel et al. (Camlibel). Dependent claim 8 was rejected under 35 U.S.C. §103 over Wada and Camlibel in further view of U.S. Patent No. 4,889,960 to Butt (Butt). Dependent claims 15 and 34-35 were rejected under 35 U.S.C. §103 over Wada and Camlibel in further view of U.S. Patent No. 6,111,270 to Xu et al. (Xu). Dependent claim 22 was rejected under 35 U.S.C. §103 over Wada in view of U.S. Publication No. 20050244949 to Miles (Miles).

Independent claim 1 now recites the step of “using the structure as an etching stop while producing etching pits on the underside so that the etching pits extend through the substrate to the structure (emphasis added)”.

Applicants respectfully submit that the proposed combination of references fails to disclose or suggest now present claim 1.

Wada discloses that a hole 50 is formed in films 16, 38 at the upper side, while a hole 52 is formed in film 40 at the upper side. Then, the part of the wafer 5 exposed by holes 50 and 52 is etched to form depressions 54 and 56. Depressions 54 and 56 are used as locating holes for a laser, which forms a pore 58 through the wafer 5. Finally, the pore 58 is enlarged to form a through hole 4. See paragraphs [0090-0093].

Applicants respectfully submit that Wada, which forms holes 50, 52 on both sides of the wafer 5, clearly fails to disclose or suggest the step of “using the structure as an etching stop while producing etching pits on the underside” as in claim 1.

The Office Action fails to assert that any of the remaining cited references (e.g., Camlibel, Butt, Xu, and Miles) alone or in combination with one another disclose or suggest producing etching pits as in claim 1.

Accordingly, claim 1 is believed to be in condition for allowance. Claims 2-22 and 34-40 are also believed to be in condition for allowance for at least the reason that they depend from claim 1. Reconsideration and withdrawal of the rejections to claims 1-22 and 34-40 are therefore respectfully requested.

Independent claim 23, as well as dependent claims 23, 26-27, and 31-32, were rejected under 35 U.S.C. §102 over Wada. Similarly, independent claim 25 was rejected under 35 U.S.C. §103 over Wada and Camlibel in further view of Xu. Dependent claim 24 was rejected under 35 U.S.C. §103 over Wada in view of Camlibel. Dependent claims 29-30 were rejected under 35 U.S.C. §103 over Wada and Camlibel in further view of Xu. Dependent claim 28 was rejected under 35 U.S.C. §103 over Wada and Camlibel in further view of Butt.

Independent claims 23 and 25 each now recite a plurality of etched pits “extending through the substrate and stopping at the one or more semiconductor structures and/or connection structures (emphasis added)”.

Again, Wada discloses forming holes 50, 52 on the opposite sides of the wafer 5 and using these holes to etched depressions 54,56 in both sides of the wafer. Clearly, no portion of Wade discloses the plurality of etched pits that extend through the substrate and stop at the structures as in claims 23 and 25.

The Office Action fails to assert that any of the remaining cited references (e.g., Camlibel, Butt, Xu, and Miles) alone or in combination with one another disclose or suggest etched pits that stop at the structures as in claims 23 and 25.

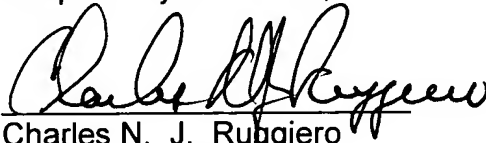
Therefore, independent claims 23 and 25, as well as claims 24 and 26-32 that depend therefrom, are not disclosed or suggested by Wada, alone or in combination with Camlibel, Butt, and Xu. As such, claims 23-32 are in condition for allowance. Reconsideration and withdrawal of the rejections to claims 23-32 are respectfully requested.

In view of the above, it is respectfully submitted that the present application is in condition for allowance. Such action is solicited.

If for any reason the Examiner feels that consultation with Applicants' attorney would be helpful in the advancement of the prosecution, the Examiner is invited to call the telephone number below.

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Respectfully submitted,



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